

Title (en)  
METHOD AND DEVICE FOR PRODUCING A STRUCTURED SURFACE

Title (de)  
VERFAHREN ZUR ERZEUGUNG EINER STRUKTURIERTEN OBERFLÄCHE

Title (fr)  
PROCÉDÉ ET DISPOSITIF DE FABRICATION D'UNE SURFACE STRUCTURÉE

Publication  
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Abstract (en)  
[origin: WO2018229164A1] The invention relates to a method for producing a decorative and textured surface having differing degrees of gloss, comprising the following steps: - feeding a workpiece (1.0) to a device for the application of a varnish, - applying, across the whole surface, a first liquid varnish layer (1.4) with course texturing wherein there is a thickness difference between thicker regions and thinner regions of at least 50 µm and particularly at least 100 µm, - and particularly digitally spraying droplets onto subsurfaces of the first varnish layer (1.4) on the workpiece (1.0), preferably using an at least partially transparent varnish, for the application of a second varnish layer (1.5) onto the first varnish layer (1.4), wherein said second varnish layer (1.5) has a different degree of gloss to the first varnish layer (1.4) after curing. The invention also relates to a device for carrying out the claimed method.

Abstract (de)  
Es wird ein Verfahren zur Erzeugung einer dekorativen Oberfläche auf einem Werkstück (1) mit folgenden Schritten offenbart:- Zuführen (S10) des Werkstückes (1), das mit einer flüssigen Schicht (2) beschichtet ist, zu einer digitalen Druckstation;- Aufbringen (S12) eines Mittels, das dazu ausgebildet ist, elektromagnetische Strahlung zumindest teilweise zu absorbieren, zumindest auf eine Teilfläche der Oberfläche der flüssigen Schicht (2), oder welches in Kontakt mit der Oberfläche ein Reaktionsprodukt entstehen lässt, das derart beschaffen ist, dass es elektromagnetische Strahlung zumindest teilweise zu absorbieren vermag;- Bestahlen (S14) der Oberfläche der flüssigen Schicht (2) und des Mittels mit elektromagnetischer Strahlung.Ferner wird eine Vorrichtung (18) zur Durchführung dieses Verfahrens offenbart.

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